

## Trends of Major Research Facilities Related to Materials Science and Engineering

Science and technology have always been strongly influenced by materials science and engineering (MS&E) because of materials needed to implement technology and lead science. And although MS&E disciplines are best known as fields of individual investigator science, they have become a significant influence on the development and use of major facilities and vice versa. In this article, I explore some of the trends in MS&E as they relate to major facilities.

In recent years, the design and understanding of new materials often require relating the microscopic properties and interactions of atoms at the atomic level to the macroscopic behavior of the material, and increasingly, this requires the use of some major facility. Also, powerful probes such as synchrotron and neutron sources have opened entirely new areas of investigation to scientists in a broad range of disciplines.

MS&E have also altered user trends at major facilities. Unlike high energy nuclear physics facilities, where a few "big science" experiments are done year round, major facilities for MS&E are used by numerous groups of individuals doing many experiments on many beam lines as an extension of their own laboratory studies. Another trend is the increasing use of the facilities by industry. As little as 10 years ago, most users of Oak Ridge National Laboratory's (ORNL) materials facilities were academic scientists, but now almost one-third of the users are from industry and that fraction is growing. Also, the diversity of disciplines using major facilities is increasing. Ten to 15 years ago, the major use of neutron scattering facilities was for condensed matter studies, but today, new users include chemists, biologists, astronomers, polymer scientists, medical researchers, environmental analysts, nondestructive testers, engineers, and drug and automotive manufacturers just to mention a few.

Much has been written by politicians and policymakers about the necessity of prioritizing major science projects, and although astronomy and high energy physics are often cited as fields which

have done this well, it is worth noting that the MS&E disciplines have done an exemplary job. Many reports written in the early 1970s through the 1990s justified the need for facilities in MS&E. Perhaps the best known of these was the National Research Council report *Major Facilities for Materials Research and Related Disciplines*<sup>1</sup> (so-called Seitz-Eastman report for its two well-known co-chairs Frederick Seitz and Dean E. Eastman). This pioneering report made recommendations for the development and construction of facilities in two categories: (1) major new facilities; and (2) new capabilities at existing facilities. The recommendations for construction of major new facilities were (1) a six GeV synchrotron radiation facility; (2) an advanced steady state neutron facility; (3) a one to two GeV synchrotron facility; and (4) a high intensity pulsed neutron facility.

In January 1986 in a memorandum entitled "Secretarial Site Selection Decisions on Specific Energy Research Projects," the Under Secretary of the Department of Energy (DOE) reflected these priorities of the scientific community and sited four specific Energy Research (ER) projects as part of a long-range plan to revitalize the DOE/ER laboratories. This siting memo stated that these "site decisions were made to maintain the technical viability among the Department of Energy laboratories." The facilities and selected sites were (1) Relativistic Heavy Ion Collider, Brookhaven National Laboratory; (2) One to Two GeV Synchrotron Radiation Source, Lawrence Berkeley Laboratory; (3) Six GeV Synchrotron Radiation Source, Argonne National Laboratory; and (4) Advanced Steady State Research Reactor, Oak Ridge National Laboratory. Although the order of these facilities have changed, the DOE/ER has done remarkably well in following through on this long-range revitalization plan and has now completed or started all but one of these facilities.

The remaining uncompleted facility is the research reactor recommended for Oak Ridge National Laboratory. And although design for a new research reactor, the Advanced Neutron Source (ANS),

was in both the 1994 and 1995 President's Budgets as a construction line item, it was not approved by Congress either year because of total cost. In response, the DOE replaced it in the FY 1996 budget with a request for design of a lower-cost, accelerator-based spallation neutron source. At this writing, the request remains in the budget and the neutron science community may finally be on its way to acquiring a much needed new neutron source.

Has the return to science and technology been worth the investment in major facilities? Although such questions are difficult to answer, the best indication may come from considering the oldest major facilities, neutron sources, and their impact on science and, thereby, society. The 1994 Nobel Prize in Physics was shared by Clifford Shull for pioneering work he did at the ORNL Graphite Reactor in the early 1950s, and by Bertram Brockhouse for similar studies at a comparable reactor at the Chalk River Nuclear Laboratories in Canada. Their work, which initiated the modern field of neutron scattering, would have been impossible without these first "major" neutron reactor facilities accessible to them at the time. Furthermore, these same facilities and their successors produced the first medical isotopes, initiated radiation damage studies and alloy development, facilitated nuclear power production, supported recent industrial developments, and much more. In the area of science alone, at least eight other Nobel Prizes have been granted between 1950 and 1994 for work done at major neutron facilities. This enviable record for science and technology is a strong testimonial of the synergism between major facilities and MS&E, and the ultimate benefit to society.

BILL APPLETON

*Bill Appleton is Associate Laboratory Director for Advanced Materials, Physical, and Neutron Sciences at Oak Ridge National Laboratory.*

1. *Major Facilities for Materials Research and Related Disciplines.* (National Academy Press, Washington, D.C., 1984).

### COSE WORKSHOP ON OPTICAL INFORMATION TECHNOLOGY

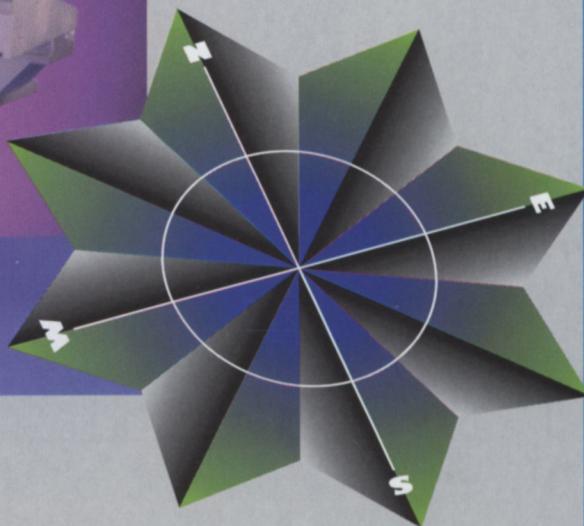
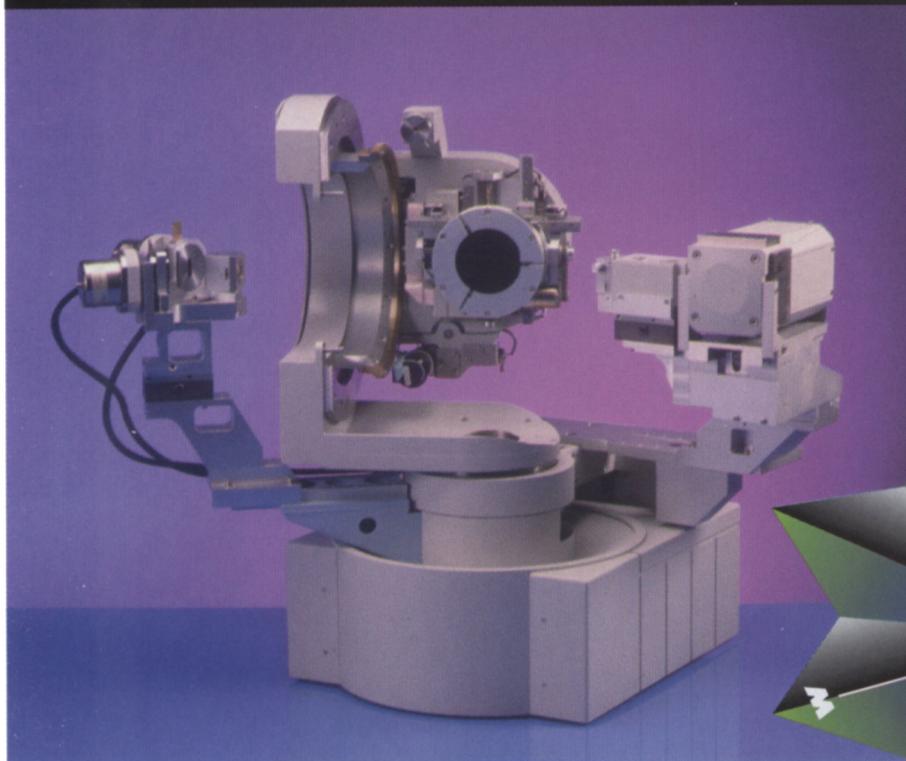
Washington, DC — November 30–December 1, 1995

• Information Transport • Information Storage • Information Processing • Display

For information, contact the Committee on Optical Science and Engineering (COSE) of the National Research Council at 202-334-3520, fax: 202-334-2791, e-mail: cose@nas.edu, or the NAS homepage: URL: <http://www.nas.edu>.

# New horizons in materials research

## NEWS



The brand new X'Pert-Materials Research Diffractometers from Philips offer you the easiest access to direct solutions in materials research.

Optimum performance, versatility and immediate results in:

- High resolution
- Thin film
- Reflectometry
- Texture
- Stress
- Phase

### Seeing is believing

Please ask for a free demonstration disk



Visit MRS Exhibit  
Booth Nos. U800-U801

Philips  
Analytical  
X-Ray

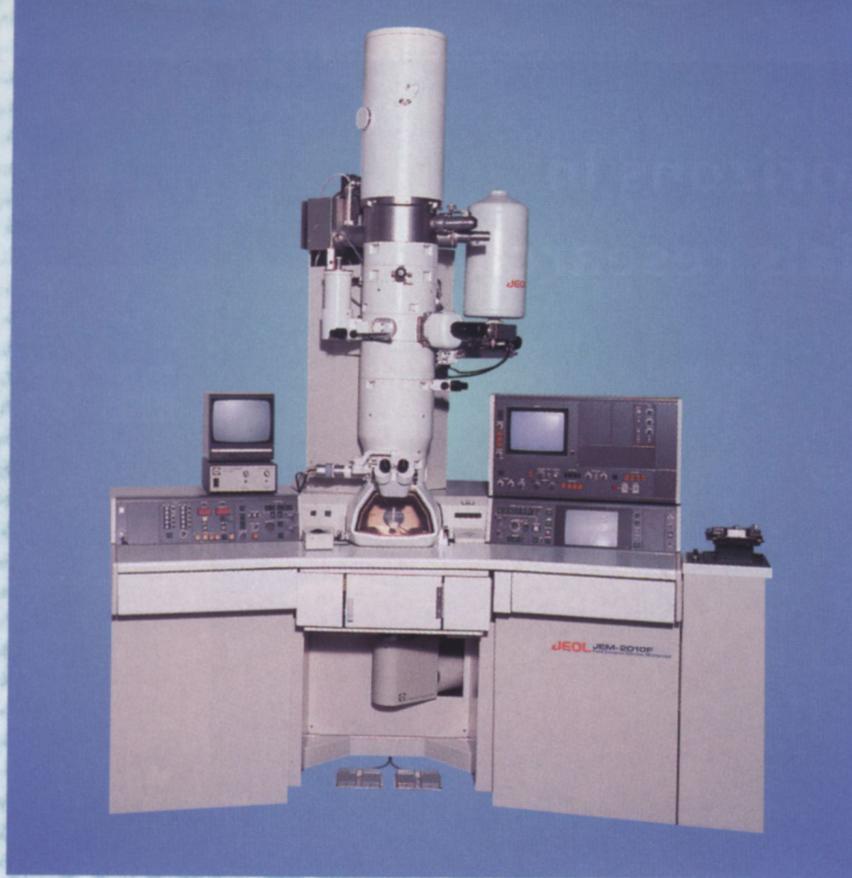


**Philips Analytical X-Ray BV**  
Lelyweg 1, 7602 EA Almelo,  
The Netherlands.  
Tel. +31 (546) 839430.  
Fax +31 (546) 839598.

**Philips Electronic  
Instruments Company**  
85 McKee Drive, Mahwah,  
NJ 07430, USA.  
Tel. +1 (201) 5296246.  
Fax +1 (201) 5295084.

# PHILIPS

Circle No. 37 on Reader Service Card.



# Sights Unseen.

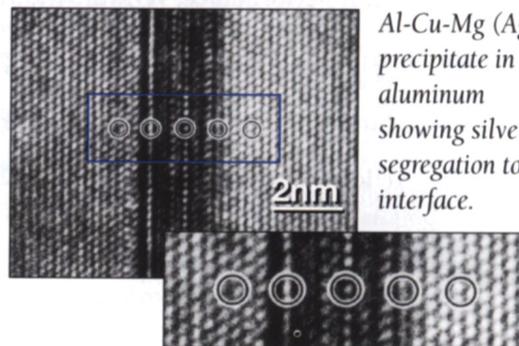
With the New JEM-2010F **Field Emission** Electron Microscope  
You'll See It ... If It's There.

Visit MRS Exhibit  
Booth No. A7

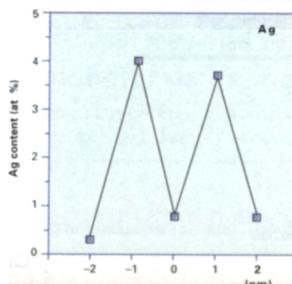
From JEOL...the newest generation of precision equipment that permits unprecedented resolution in 3-dimensional, subnanometer analysis of microstructures. Featuring user-friendly operation and long-term stability, the JEM-2010F also offers:

- Schottky Emission: High Current High Brightness
- High Probe Current: 0.5nm Probe with 100 pA Current
- High Resolution: Information Limit 1.4Å, Scherzer 1.9Å
- Holography: Option Available
- STEM Resolution: 0.2nm Magnification: 8MX

Discover the JEM-2010F and visit sights previously unseen.



Al-Cu-Mg (Ag) precipitate in aluminum showing silver segregation to interface.

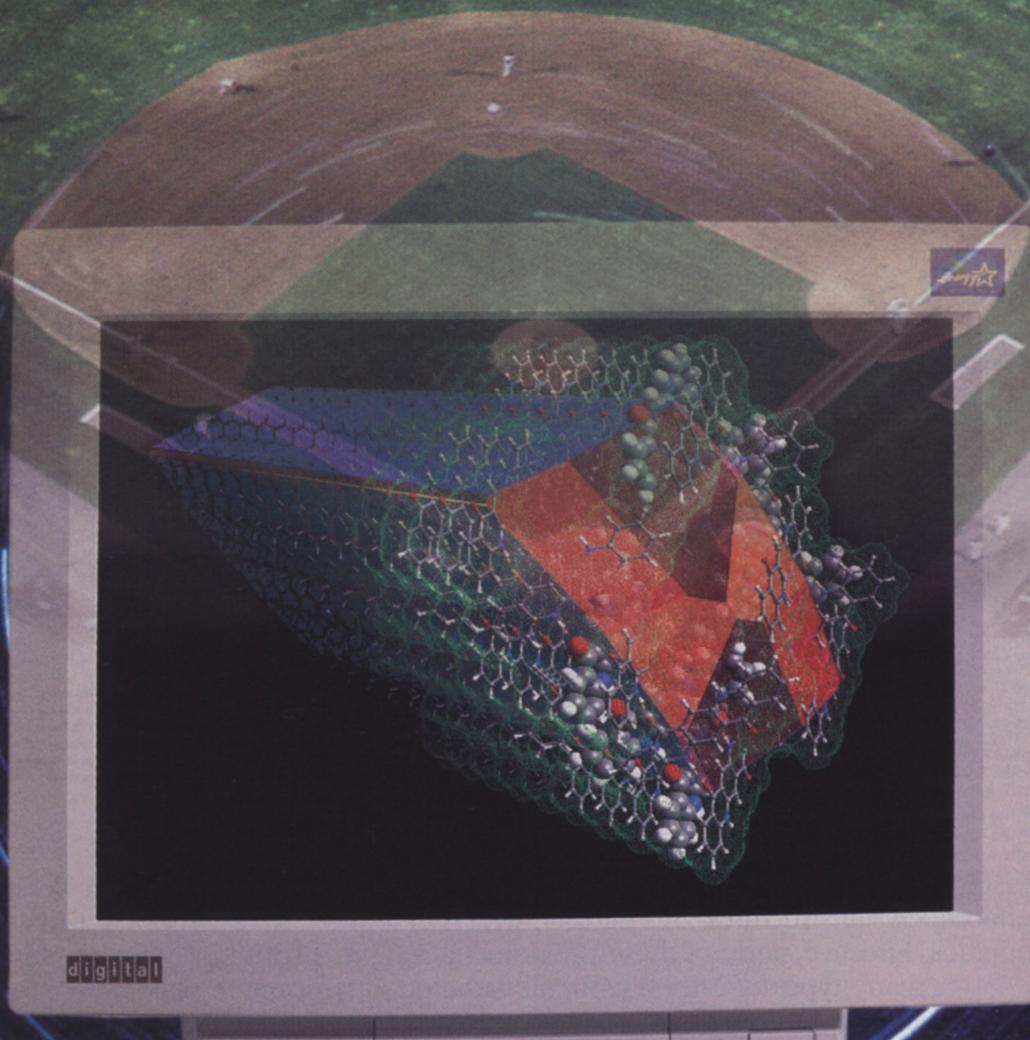


Data courtesy of Dr. James M. Howe, Department of Materials Science & Engineering, University of Virginia, U.S.A.



JEOL USA, Inc., 11 Dearborn Road, Peabody, MA 01960  
Tel: 508-535-5900 Fax: 508-536-2205 e-mail: eod@jeol.com

# There's been a change in the line-up.



crystallite of  
the pigment  
quinacridone

digital

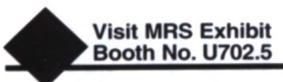
## BIOSYM/Molecular Simulations is leading that change.



### Leading the way with Cerius<sup>2</sup>

Cerius<sup>2</sup> is changing the strategies used in chemical computing. It is first in its league in applying the best computational techniques to real world research problems. That's why there are more new users of Cerius<sup>2</sup> in R&D departments than ever before, many of them switching from previous generation products to this innovative environment.

Cerius<sup>2</sup> is used at over 600 different research sites around the world, in industries from oil and gas, through pharmaceuticals and chemicals, to aerospace. It's made big hits in the determination of crystal structure, design of catalysts, control of morphology, prediction of polymer properties, and interpretation of data from analytical instruments.



Moving Ahead Together

United States + 1 619 546-9990 • United Kingdom + 44 (1223) 413300 • Continental Europe + 41 61 271 8881 • Japan + 813 3818 6511  
BIOSYM/Molecular Simulations World Wide Web Address: <http://www.biosym.com>

**Visit us at our MRS exhibit to see how BIOSYM/Molecular Simulations solutions are changing the way the game of chemical computing is being played!**

Circle No. 10 on Reader Service Card.

# Points of view for advanced materials analysis



Philips' new CM300 series TEMs feature a high 300 kV with either  $\text{LaB}_6$ ,  $\text{CeB}_6$ , W or FE emitter, and our patented TWIN, Super-TWIN, or UltraTWIN objective lens.



The new XL40 FEG SEM features a 150 mm motorized eucentric stage, conical end-lens and large chamber with full system automation and integrated image analysis.

Increasingly materials research is concerned with structures at the atomic scale such as interfaces, crystal structures and defects, which determine many important materials properties. Effective study of these phenomena require instruments that combine many types of information, all gathered at nanometre scale.

Our scanning and transmission electron microscopes blend high image quality and system performance with exceptional ease of use to provide you with the very best points of view. And of course, you can depend on Philips for full support. If you would like to develop your own points of view about Philips electron microscopy,

fax or call for information:

Fax: 201-529 2252, Telephone: 201-529 3800

E-mail: [marcom@eo.ie.philips.nl](mailto:marcom@eo.ie.philips.nl)

Philips Electronic Instruments Co.

85 McKee Drive, Mahwah, NJ 07430

***Philips Electron Optics -  
More than 50 Years of Innovation***



Visit MRS Exhibit  
Booth Nos. U800-U801

EO 95-02



**PHILIPS**

Circle No. 38 on Reader Service Card.

# CORPORATE AFFILIATES

(As of September 1995)

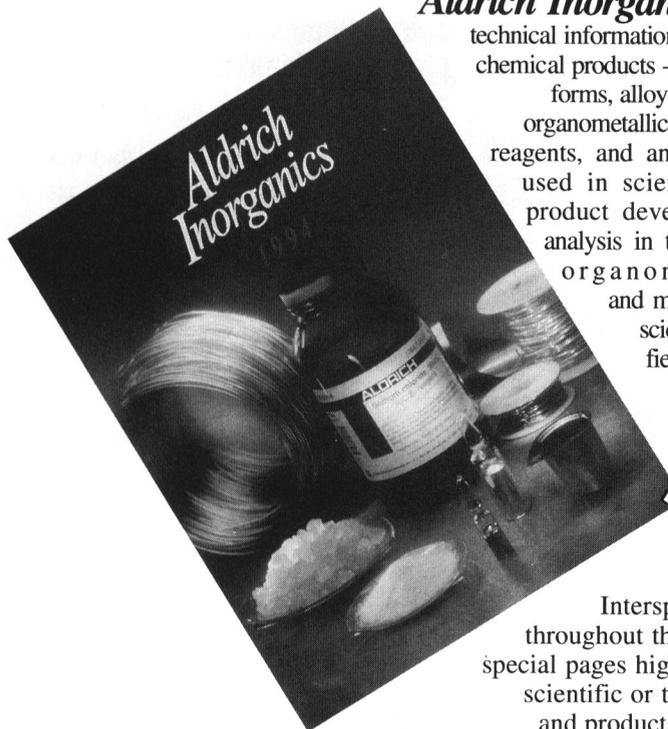
## Materials Research Society would like to thank the following for their financial support:

- Addax SA  
Advanced Control Systems Corp.  
Advanced Energy Industries, Inc.  
Advanced Micro Devices, Inc.  
Advanced Photovoltaic Systems, Inc.  
AEA Technology  
Aerospace Corp.  
AG Associates  
Air Products and Chemicals, Inc.  
AIXTRON, Inc.  
Akzo  
Aldrich Chemical Company  
Allied-Signal, Inc./Advanced Microelectronic Materials  
Allied-Signal, Inc./Research & Technology  
Aluminum Company of America  
Aluminum Research Board  
American Chemical Society  
American Xtal Technology  
AMRAY, Inc.  
Anatech, Ltd.  
APD Cryogenics, Inc.  
Applied Materials  
ASTeX  
Argonne National Laboratory  
Asahi Glass Co., Ltd.  
AST elektronik GmbH  
AT&T Bell Laboratories  
ATRIX Laboratories, Inc.  
Automotive Composites Consortium  
Balzers  
Bayer Corporation  
Bellcore  
BIOSYM/MSI  
Blake Industries, Inc.  
Brookhaven Instruments Corp.  
Brookhaven National Laboratory  
Cabot Corp.  
Cameca Instruments, Inc.  
Canon, Inc.  
Centre Européen pour le Recherche Nucleaire (CERN)  
CFM Technologies, Inc.  
Chemat Technology, Inc.  
China Technical Consultants, Inc.  
CNRS  
Cober Electronics  
Coherent Laser Group  
Commonwealth Scientific Corp.  
Communications and Power Industries, Inc.  
Comstock, Inc.  
Conductus, Inc.  
Consortium für Elektrochemische Ind. GmbH  
Corning, Inc.  
Courtaulds  
CREE Research, Inc.  
CVC Products, Inc.  
Cymer Laser Technologies  
Dainippon Screen Mfg. Co., Ltd.  
DCA Instruments, Inc.  
Denton Vacuum, Inc.  
Digital Equipment Corp.  
Digital Instruments, Inc.  
Dow Chemical Co.  
Dow Corning Corp.  
DSM Research  
Dytech International  
Eastman Kodak Company  
Eaton Corp.  
EG&G Nuclear Instruments  
E.I. duPont de Nemours & Co., Inc.  
Electric Power Research Institute (EPRI)  
Electricité de France  
Elsevier Science Publishing Co., Inc.  
EMCORE Corp.  
Energy Conversion Devices  
Engelhard Corp.  
Enraf-Nonius Co.  
EPI/MBE Products Group
- ES Microwave  
Charles Evans & Associates  
Evans East  
Extrel Corp.  
Exxon Production Research Co.  
Exxon Research and Engineering Co.  
Federal Highway Administration  
FEI Co.  
E.A. Fischione Instruments, Inc.  
Fisons Instruments  
Ford Motor Co.  
Fuji Electric Co., Ltd.  
Fujikin of America, Inc.  
Gas Research Institute  
Gatan, Inc.  
Gelest, Inc.  
Genentech, Inc.  
General Electric Co.  
General Motors Research  
Genus, Inc.  
Golden Technologies  
Goodfellow Corp.  
Gordon & Breach Publishers, Inc.  
Granville-Phillips Co.  
Groupe de Dynamique des Phase Condenses  
Haldor Topsøe A/S  
Hauzo Techno Coating Europe  
Hewlett-Packard Co.  
High Voltage Engineering Europa B.V.  
Hitachi, Ltd.  
Hitachi Scientific Instruments  
Hoechst AG  
Hoechst Celanese Research Division  
Howmedica  
Hughes Research Laboratories  
Huntington Mechanical Laboratories  
IBM AdStaR  
IBM Analytical Services  
IBM Corp.  
IHI Research  
Inorgtech  
Institut für Schicht und Ionentechnik (ISI)  
Institute for Scientific Information (ISI)  
Institute of Physics Publishing (IOP)  
Instron Corp.  
Instruments SA, Inc./Riber Division  
Intel Corp.  
International Center for Materials Research (ICMR)  
Ion Tech, Inc.  
ITAC, Ltd.  
JCPDS-International Centre for Diffraction Data  
JEOL USA, Inc.  
Johnsen Ultravac  
Johnson Controls, Inc.  
Johnson & Johnson  
Johnson & Johnson Professional  
Kaneka Corp.  
Kawasaki Steel Corp.  
Keithley Instruments, Inc.  
Kimball Physics, Inc.  
Kobe Steel USA, Inc.  
Komag, Inc.  
Kratos Analytical, Inc.  
Kyocera Corp.  
Lafarge Fondu International  
Lake Shore Cryotronics, Inc.  
Lambda Physik, Inc.  
Lawrence Berkeley Laboratory  
Lawrence Livermore National Laboratory  
Lawrence Semiconductor Research Laboratory  
Legacy Systems, Inc.  
Kurt J. Lesker Co.  
Lockheed Idaho Technologies Co.  
Lockheed Martin Energy Systems  
Los Alamos National Laboratory  
Lumonics, Inc.  
Magnet Sales & Manufacturing Co.
- Marcel Dekker, Inc.  
Martin Marietta Energy Systems, Inc.  
Materials Research Corp.  
Materials Research Group  
MCP Water Technology, Ltd.  
MDC Vacuum Products Corp.  
Medisorb Technology International  
MEL Chemicals  
MEMC Electronic Materials  
MER Corp.  
Microwave Materials Technologies, Inc.  
Millipore Corp.  
Mitsubishi Electric Semiconductor Laboratories  
Mitsubishi Materials Corp.  
Mitsui Engineering & Shipbuilding Co., Ltd.  
Mitsui Toatsu Chemicals, Inc.  
MKS Instruments, Inc.  
Morton Advanced Materials  
Motorola APRDL  
MR Semicon, Inc.  
MVSystems, Inc.  
n&k Technology  
Nano Instruments, Inc.  
Nanophase Technologies  
Nanotec Corp.  
NASA Lewis Research Center  
National Electrostatics Corp.  
National Renewable Energy Laboratory (NREL)  
National Semiconductor  
NEC Corp.  
NEC Research Institute, Inc.  
Neocera, Inc.  
New Focus, Inc.  
Niki Glass Co.  
Nikko Hitech International, Inc.  
Nippon Oil Corp.  
Nippon Steel Corp.  
Nissei Sangyo America, Ltd.  
Nor-Cal Products, Inc.  
Northern Telecom, Ltd.  
Novapure Corp.  
Nuclear Regulatory Commission  
Oak Ridge National Laboratory  
Omicron Associates  
OnTrak Systems, Inc.  
OPTOVAC  
Oxford Applied Research  
Park Scientific Instruments  
Paterson Instruments PTY, Ltd.  
Perseptive Biosystems, Inc.  
Philips Electronic Instruments Co. (PEI)  
Physical Electronics  
Plasma Sciences, Inc.  
Plasma-Therm, Inc.  
Plenum Publishing Co.  
Portland Cement Association  
Precision Manufacturing Center  
President Enterprises Co.  
Princeton Gamma-Tech, Inc.  
Pure Tech, Inc.  
Quantum Design, Inc.  
Read-Rite Corp.  
Research and PVD Materials Corp.  
Rexham Custom  
RHK Technology  
Rigaku/USA, Inc.  
RIMCOF  
Rockwell International Corp.  
ROITECH  
Sandia National Laboratories  
Santa Clara Plastics  
Sanyo Electric Co., Ltd.  
Schlumberger Doll Research  
Schumacher/Air Products & Chemicals Unit  
Seagate Technology, Inc.  
Sematech, Inc.  
Semiconductor Processing Co.
- SGS-Thomson Microelectronics  
Sharp Corp.  
Siemens Analytical X-Ray Instruments, Inc.  
Siltec Silicon  
Smith & Nephew Research, Ltd.  
Solarex Corp.  
Solartron Instruments  
Solid State Equipment Co.  
Sony Co., Ltd.  
SOPRA, Inc.  
South Bay Technology, Inc.  
Southwest Research Institute  
Spectra-Physics Lasers, Inc.  
Spire Corp.  
Springer-Verlag New York, Inc.  
Staub Instrumente GmbH  
Strem Chemicals, Inc.  
SubMicron Systems, Inc.  
Sumitomo Electric USA, Inc.  
Sumitomo Sitix Corporation  
Superior Vacuum Technology, Inc.  
Surface/Interface, Inc.  
TDA Research  
Telemark  
Tencor Instruments  
Texas Instruments, Inc.  
Thermionics Laboratory, Inc.  
3M Fiber Optics  
Tokyo Instruments, Inc.  
Topcon Technologies, Inc.  
TopoMetrix Corp.  
Toray Industry, Inc.  
Toshiba Corporation  
Toyota Central R&D Laboratories, Inc.  
Ultram International  
United Solar Systems Corp.  
Universal Instruments Corp.  
USG Corporation Research Center  
Vacuum Barrier Corp.  
Vacuum Metallurgical Co.  
Vacuum Science Instruments GmbH (VSI)  
Varian Associates, Inc.  
Varian Associates, Inc./Continental Electronic Division  
VCH Publishers, Inc.  
Verein IWEF  
Virginia Semiconductor, Inc.  
VITA-IP, Inc.  
Voitax, Inc.  
John Wiley & Sons, Inc.  
J.A. Woollam Co.  
W.R. Grace & Co.  
Wright Patterson AFB  
Xerox Corp.  
Carl Zeiss, Inc.

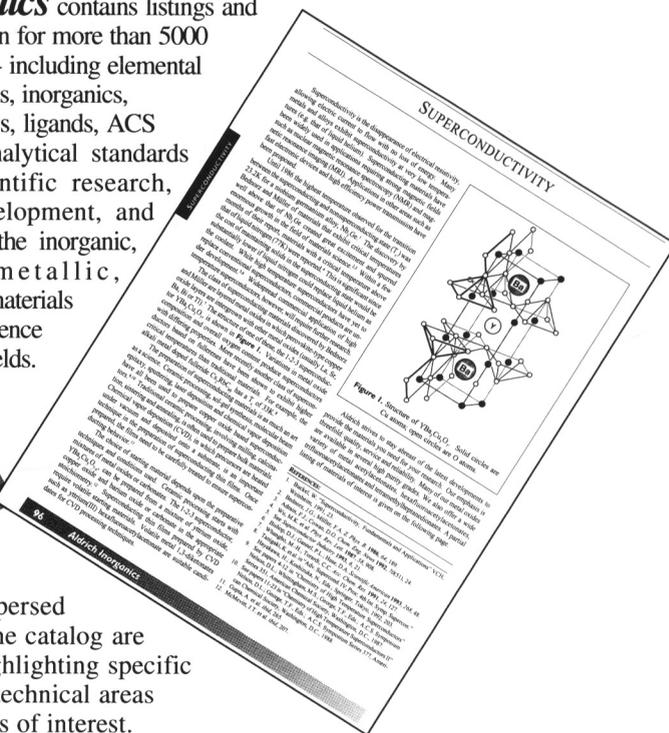
### For more information about the Corporate Participation Program contact:

Mary E. Kaufold  
Materials Research Society  
9800 McKnight Road  
Pittsburgh, PA 15237  
Telephone (412) 367-3036  
Fax (412) 367-4373  
E-mail: kaufold@mrs.org  
or

Dr. Michael Current  
Corporate Participation  
Committee Chair  
Applied Materials  
Implant Division MS 0017  
Great Hills Corporate Ctr.-1 Ste. 270  
9020-1 Capital of Texas Hwy. North  
Austin, TX 78759  
Telephone (512) 272-7012  
Fax (512) 272-7272  
E-mail: Michael\_Current%AMAT@  
MCIMail.com



**Aldrich Inorganics** contains listings and technical information for more than 5000 chemical products - including elemental forms, alloys, inorganics, organometallics, ligands, ACS reagents, and analytical standards used in scientific research, product development, and analysis in the inorganic, organometallic, and materials science fields.



Interspersed throughout the catalog are special pages highlighting specific scientific or technical areas and products of interest.

**If you are looking for:**

**Product Selection**

More than 5000 products ready for shipment, including many advanced materials made in our own production laboratories

**Technical Support**

Includes years of experience in many specialized fields, combined with a database of technical and analytical information at your disposal

**Quality Assurance**

Based on technical expertise and state-of-the-art instrumentation dedicated to this segment of our business

**The Newest Tool for Chemists from Aldrich**

You have a new Choice...  
**THE BEST CHOICE**  
**Aldrich Inorganics**

**Call Today for a FREE Copy!**

<b>USA &amp; Canada</b> (800) 227-4563	<b>International</b> (414) 273-3850	<b>or Fax</b> (414) 273-2094
---	--	---------------------------------



Visit MRS Exhibit Booth No. U407

Circle No. 5 on Reader Service Card.